

ABSTRACT

The invention includes an apparatus and a method of manufacturing such apparatus using a damascene process. The method includes the step of patterning a layer disposed over a substrate to include a line and space pattern. The line and space pattern in the layer includes at least one space comprising a width dimension of a feature to be formed. The feature may be, e.g., a wordline(s)/gate electrode(s). Additionally, the sidewalls of the feature, e.g., the wordline(s)/gate electrode(s) include relatively smooth surfaces.

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